

Plenary 5

- Date / Time: January 19 (Tue.), 2021 / 11:00-11:50
- Session Chair: Heeyeop Chae (Sungkyunkwan Univ., Korea)

**Plasma Technology Trends in Semiconductor Equipment Industry**

CEO. Changjin Kang
(SEMES, Korea)

Abstract

The COVID-19 pandemic, in addition to the growth of data storage and AI, has ultimately reshaped our daily lives – now many things are done contactless and virtual. With the increasing use of cloud, server, networks, and computing, semiconductor bit growth need is increasing rapidly, whereas as the speed of shrinking chip size is decreasing due to technological difficulties. Therefore, now is the time for leading chipmakers to increase fab investment to meet the bit growth demand, and for equipment makers to develop high-performing and cost-effective equipment to reduce the investment cost.

Plasma plays a vital role in fab processes and equipment: a core technology in dry etch, chemical vapor deposition (CVD) and sputter deposition, and even in EUV light source for the next-gen lithography. In this talk, the application and forecast of plasma technology in the semiconductor equipment industry will be discussed.

Biography

Changjin Kang joined SEMES as Chief Executive Officer in January 2019. He has more than 30 years of experience in the semiconductor industry. Prior to this role, he had worked at Samsung Electronics in various R&D and business executive roles, including most recently as Executive Vice President of the Strategic Planning Team until 2018; Senior Vice President of the Corporate Consulting Team and the Auditing Team from 2014 to 2017; and Vice President of the Process Development Team at Semiconductor R&D Center where he started his career as a process engineer. He holds a Ph.D. and an M.S. in Material Science Engineering from Korea Advanced Institute of Science, and a B.S. in Metallurgical Engineering from Seoul National University.